

Title (en)
DOPING OF CRYSTALLINE SUBSTRATES

Title (de)
DOTIEREN VON KRISTALLINEN SUBSTRATEN

Title (fr)
PROCEDE DE DOPAGE DE SUBSTRATS CRISTALLINS

Publication
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Application
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Abstract (en)
[origin: WO0073543A1] A method is provided of producing a doped crystalline substrate having a crystal lattice. The method involves providing a crystalline substrate having a crystal lattice and implanting dopant atoms into the substrate to create a doped layer. Thereafter, or at the same time, ions are implanted into the substrate to create a damaged layer which is separate from the doped layer and contains vacancies and interstitials of the crystalline substrate. The interstitial atoms are caused to diffuse out of the damaged layer into vacancies in the doped layer to reduce the damage therein.

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